



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: CHENG et al.

Examiner: Everhart, Caridad

Application No. 10/738,360

Group No.: 2829

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Title: METHODS AND APPARATUS FOR
THE OPTIMIZATION OF PHOTO RESIST
ETCHING IN A PLASMA PROCESSING
SYSTEM

INFORMATION DISCLOSURE STATEMENT

US PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number	Publication Date	Name of Patentee or Applicant	Reference to Related Case
CME	1	6,083,844	2000-07-04	Bui-Le et al.	
CME	2	6,297,163	2001-10-02	Zhu et al.	
CME	3	6,235,644 B1	2001-05-22	Chou	

OTHER DOCUMENTS

Examiner Initials	Cite No.	Description	T
CME	4	Ellingboe, Bert, "Plasma Processing In The Microelectronics Industry", Plasma Research Laboratory, paper.	
CME	5	"Research", http://graves-lab.cchem.berkeley.edu/~humbird/research/	
CME	6	Lassig et al., "Selective Removal Strategies for Low k Dual Damascene", Semiconductor Fabtech, pp 185-190	
CME	7	EEE435/591 Microelectronics: Lecture 16: Back-end Processes	
CME	8	EE 539TM/M(S)E 599TM - Lecture C2: Lithography-based Systems	
CME	9	Hanawa, Tesuro (Group 1), "Current Status of Photolithography/Etching", Semiconductor Leading Edge Technologies, Inc. May 31, 2000 Selete Program Update	
CME	10	Jones et al., "Micro Photocell Monitoring Finds the Killers", Summer 2003, Yield Management Solutions, pp. 38-45	
CME	11	Woods, Eric, "Plasma Etching", CMOS Group, Microelectronics Research Center, Georgia Institute of Technology	
CME	12	Muscat, Anthony, "Gas Phase Cleaning of Silicon Wafer Surfaces", http://www.che.arizona.edu/directory/faculty/muscat/research/Tutorials/Gas_Phase_Wafer_Clean.html	
CME	13	Spitzlsperger, Gerhard, "Introduction to Low Pressure Glow Discharges for Semiconductor Manufacturing with Special Emphasis on Plasma Etching", http://www.gs68.de/tutorials/plasma/node26.html	

Examiner Signature	<i>C. Everhart</i>	Date Considered	<i>4-15-05</i>
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